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# **Supporting Information**

# Barium disilicide as a promising thin-film photovoltaic absorber: structural, electronic, and defect properties

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### 1. Born-effective charges

The Born-effective charges  $Z^*$  is a fundamental quantity that manifest the strength of the charge transfer with respect to the displacement of atom. It is also a useful tool to investigate the degree of covalency and ionicity in particular bonding to some extent. The calculated sum of the Born effective charges fulfil the acoustic sum rule  $\sum Z_{s,ij}^* = 0$ .

In a conventional unit cell of BaSi<sub>2</sub>, eight Ba occupy two inequivalent 4*c* Wyckoff sites. We designated these as B(I) with fractional coordinate x = 0.017, y=0.25, z = 0.692) and B(II) with x = 0.839, y=0.25, z = 0.092. Similarly, 16 Si occupy three inequivalent positions at 4*c* and 8*d* Wyckoff sites, we designated these as Si(I) with x = 0.416, y=0.25, z = 0.091), Si(II) with x = 0.198, y=0.25, z = 0.966), and Si(III) with x = 0.195, y=0.734, z = 0.145 fractional coordinates. In this case, the sum rule is as follows:  $Z^{*}[Ba(I)] + Z^{*}[Si(I)] + Z^{*}[Si(II)] + 2Z^{*}[Si(III)] = 0$ .

The formal static charge of Ba and Si in  $BaSi_2$  compound are +2 and -1 respectively. We can see from table S1 that all these compounds have large Z\* compared with their nominal static charges.

This large variation in  $Z^*$  compared to nominal static charge confirms the charge transfer in BaSi<sub>2</sub> system also show the covalent bonding character of Si atoms.

**Table S1** Calculated Born effective charge ( $Z^*$ ) of Ba<sub>2</sub>Si<sub>4</sub>. Here we presented  $Z^*_{XX}$ ,  $Z^*_{YY}$ ,  $Z^*_{ZZ}$  and  $Z^*_{avg}$  for two inequivalent sites Ba(I), B(II) of Ba atom and three inequivalent sites, Si(I), Si(II) and Si(III) of Si atoms.

	Born effective charges Z* (e)					
	Ba(I)	Ba(II)	Si(I)	Si(II)	Si(III)	
$Z^*_{XX}$	2.42	2.95	-1.18	-1.98	-1.10	
$Z_{\scriptscriptstyle YY}^{*}$	3.33	2.30	-1.22	-1.28	-1.58	
$Z_{ZZ}^{*}$	3.07	2.42	-0.94	-2.11	-1.23	
$Z^*_{avg}$	2.94	2.56	-1.11	-1.79	-1.30	



Figure S1 Calculated (a) total and orbital decomposed density of states, (b) crystal population for the different bonds in BaSi<sub>2</sub>.

	PBE	HSE06	GW0	Exp.
Eg	0.77	1.25	1.28	1.1–1.3 <sup>a</sup>
$E_g^{dir}$	0.86	1.37	1.38	
$E_g^{\Gamma}$	1.22	1.68	1.75	
$E_g^X$	1.79	2.32	2.38	
$E_g^{\scriptscriptstyle Y}$	0.97	1.48	1.48	
$E_g^Z$	1.50	2.01	2.10	
$E_g^T$	1.05	1.55	1.58	

**Table S2** Calculated fundamental band gap  $(E_g)$  and other various energy gaps of BaSi2 at various high symmetry points of BZ in the unit eV, together with the available experimental data.

<sup>a</sup> T. Suemasu, Jpn. J. Appl. Phys. 54 (7S2), 07JA01 (2015).



**Figure S2** GW+BSE absorption coefficient  $\alpha(\omega)$  of BaSi<sub>2</sub> in all three crystallographic directions xx (black line), yy (red line) and zz (blue line). One can see that there is considerable absorptions along all the directions.



**Figure S3** Relaxed geometries for the (a) (100), (b) (010) and (c) (001) surfaces of BaSi<sub>2</sub> based on a 120-atom slab model. Here, big green balls represent Ba atom, while small blue balls represent Si atom.

## 4. Defect studies



Figure S4 Local geometries of relaxed structures for (a) singly positive silicon vacancy (V<sub>Si</sub><sup>+</sup>),
(b) silicon interstitial (Si<sub>i</sub><sup>0</sup>), and (c) barium substituted for silicon (Ba<sub>Si</sub><sup>0</sup>). The relaxed Si<sub>i</sub><sup>0</sup> is off the plane coordinated with three nearest neighbour silicon atoms, while an in-plane site was suggested by the previous work [*J Appl Phys* 2014, 116 (12), 12370928], which was adopted for an initial configuration of Si<sub>i</sub><sup>0</sup> in the present study.



Figure S5 Thermodynamic stable chemical potential domain for BaSi<sub>2</sub>.



**Figure S6** The ionization levels of intrinsic defects in the DFT band gap (~0.8 eV) of BaSi<sub>2</sub>. The initial and final charge states are labeled in parentheses.



Figure S7 Density of states near band edges for anion vacancy in (a) BaSi<sub>2</sub> and (b) FeS<sub>2</sub> compounds. Black arrows indicate the defect levels.



**Figure S8** Calculated formation energies as a function of the Fermi energy (DFT band gap) for (a) and (b) substitutional and (c) interstitial dopants (Si-rich condition) in BaSi<sub>2</sub>.



Figure S9 Calculated (a) defect formation energy and (b) electron carrier density with La and Y doping in BaSi<sub>2</sub>.

Element	Structure	Chemical potential (eV/atom)
Li	Cubic	-1.902
Κ	Cubic	-1.047
Al	Cubic	-3.740
Ga	Orthorhombic	-2.909
$N_2$	Gas	-8.295
Sb	Trigonal	-4.142

 Table S3 Calculated DFT chemical potential of various external dopants.

Dopants		Defect concentration (cm <sup>-3</sup> )		
		Si_rich	Si_poor	
	Li <sub>i</sub> <sup>+1</sup>	1.3x10 <sup>19</sup>	1.1x10 <sup>19</sup>	
	N <sub>i</sub> <sup>+1</sup>	2.3x10 <sup>18</sup>	1.9x10 <sup>18</sup>	
donors	Sb <sub>Si</sub> <sup>+1</sup>	3.4x10 <sup>21</sup>	1.6x10 <sup>22</sup>	
	La <sub>Ba</sub> <sup>+1</sup>	1.3x10 <sup>17</sup>	$1.2 \times 10^{17}$	
	Y <sub>Ba</sub> <sup>+1</sup>	4.3x10 <sup>15</sup>	$4.3 \times 10^{15}$	
acceptors	K <sub>Ba</sub> -1	5.4x10 <sup>18</sup>	3.9x10 <sup>17</sup>	
	Al <sub>Si</sub> <sup>-1</sup>	9.9x10 <sup>17</sup>	$4.3 \times 10^{18}$	
	Ga <sub>Si</sub> <sup>-1</sup>	3.3x10 <sup>19</sup>	3.8x10 <sup>20</sup>	

 Table S4 Doping concentrations for considered external dopants.